

# Structure and dielectric properties of barium titanate thin films for capacitor applications

Fan He, Wei Ren\*, Guanghua Liang, Peng Shi, Xiaoqing Wu, Xiaofeng Chen

*Electronic Materials Research Laboratory, Key Laboratory of the Ministry of Education & International Center for Dielectric Research, Xi'an Jiaotong University, Xi'an 710049, China*

Available online 27 October 2012

## Abstract

BaTiO<sub>3</sub> is a typical ferroelectric material with high relative permittivity and has been used for various applications, such as multilayer ceramic capacitors (MLCCs). With the tendency of miniaturization of MLCCs, the thin films of BaTiO<sub>3</sub> have been required. In this work, BaTiO<sub>3</sub> thin films have been deposited on Pt-coated Si substrates by RF magnetron sputtering under different deposition conditions. The films deposited at the substrate temperature from 550 °C–750 °C show a pure tetragonal perovskite structure. The films deposited at 550 °C–625 °C exhibit (111) preferential orientation, and change to (110) preferential orientation when deposited above 650 °C. The film morphologies vary with working pressure and substrate temperature. The film deposited at 625 °C and 4.5 Pa has the relative permittivity of 630 and the loss tangent of 2% at 10 kHz.

© 2012 Elsevier Ltd and Techna Group S.r.l. All rights reserved.

**Keywords:** A. Films; C. Dielectric properties; D. BaTiO<sub>3</sub>; E. Capacitors

## 1. Introduction

A large number of lead-free electronic ceramics have been studied in recent years for various applications. Thin films of barium titanate (BaTiO<sub>3</sub>) and other ferroelectric materials are widely studied for applications in miniaturized devices [1]. For example, BaTiO<sub>3</sub> with high relative permittivity is a promising material for applications in gigabit density dynamic random access memories (DRAMs) and multilayered ceramic capacitors (MLCCs). To meet the demand of the miniaturization of MLCCs and at the same time to keep the same capacitance, the thickness of the dielectric layers in the MLCCs has been reduced and reached below 1 μm [2]. Thin films of BaTiO<sub>3</sub> have been prepared by several techniques, including sol–gel process [3], pulsed laser deposition [4] and RF sputtering [5].

In this work, BaTiO<sub>3</sub> thin films have been prepared by RF magnetron sputtering. The effect of substrate tem-

perature and working pressure on the structure, surface morphology and electrical properties of BaTiO<sub>3</sub> thin films have been investigated.

## 2. Experimental procedures

BaTiO<sub>3</sub> thin films were deposited by RF magnetron sputtering from the home-made ceramic targets. The substrates used in this work are Pt/Ti/SiO<sub>2</sub>/Si (100). A turbo-molecular pump backed by a rotary pump, was used to achieve a base pressure of  $2.0 \times 10^{-4}$  Pa. An RF power (Cesar1310, Dressler) was supplied to the BaTiO<sub>3</sub> target. The sputtering time was 3 h. The film thickness was measured by a stylus profiler (Dektak 6M, Veeco) and is approximately 300 nm. For electrical properties measurement, Pt top electrodes of 0.5 mm in diameter were deposited on BaTiO<sub>3</sub> films by RF sputtering.

The structures of the BaTiO<sub>3</sub> films were examined by an X-ray diffractometer (D/Max-2400, Rigaku) with Cu Kα radiation. The surface morphology and roughness are measured by an atomic force microscope (AFM, Dimension 3000, Veeco) and a field-emission scanning electron

\*Corresponding author. Tel.: +86 29 8266 6873;

fax: +86 29 8266 8794.

E-mail address: [wren@mail.xjtu.edu.cn](mailto:wren@mail.xjtu.edu.cn) (W. Ren).

microscope (FESEM, JSM-7000 F, JEOL). The dielectric properties were investigated by using a precision impedance analyzer (4294A, Agilent).

3. Results and discussion

3.1. Structure of BaTiO<sub>3</sub> thin films

XRD patterns of BaTiO<sub>3</sub> thin films deposited at different substrate temperatures are shown in Fig. 1. It can be seen that all films show a pure tetragonal perovskite structure. However, the film deposited at 550 °C exhibits quite weak crystallization. With increasing deposition temperature, (111) peak becomes weaker and the peaks of (100) and (110) gradually become stronger. Table 1 shows the analysis of the relative peak intensity (compared with Pt (111) peak) and the full width half maximum (FWHM). The strongest peak of the films is (111) for the films deposited from 550 °C to 625 °C, but changes to (110) above 625 °C which indicates a change of the preferential orientation from (111) to (110) around 625 °C [6].

It is shown that the BaTiO<sub>3</sub> ceramics has a tetragonal structure and the split in (002)/(200) peaks near 45°(2θ) indicates a tetragonal distortion. In contrast, the XRD patterns of the films, especially in (002)/(200) peaks splitting, indicate a pseudocubic phase. This result suggests that the tetragonal phase is more stable than the cubic phase in the thin films [7]. The pseudocubic phase occurs when the grain size decrease sufficiently so that the unit cell becomes less and less tetragonal as a result of the internal strain [5]. The broaden XRD peaks were observed, which manifests the decreased grain size. A core–shell model is used to explain the deformation in BaTiO<sub>3</sub> thin films [8]. In this model, a grain has a composite structure consisting of

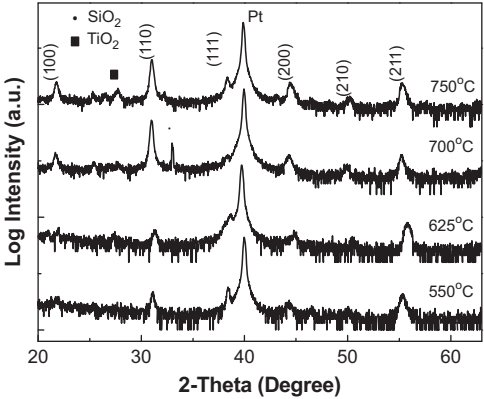


Fig. 1. XRD patterns of BaTiO<sub>3</sub> thin films deposited at temperatures from 550 °C to 750 °C.

Table 1  
Relative intensities and FWHM of XRD peaks of BaTiO<sub>3</sub> thin films deposited from 550 °C to 750 °C.

Temperature (°C)	Relative Intensity/FWHM		(02)(220)
	(101)(110)	(111)	
550	0.2%/0.36	1.0%/0.39	—
625	0.1%/0.39	0.5%/0.47	—
700	4.1%/0.20	0.1%/0.36	0.2%/0.37
750	2.2%/0.25	0.3%/0.37	0.1%/0.41

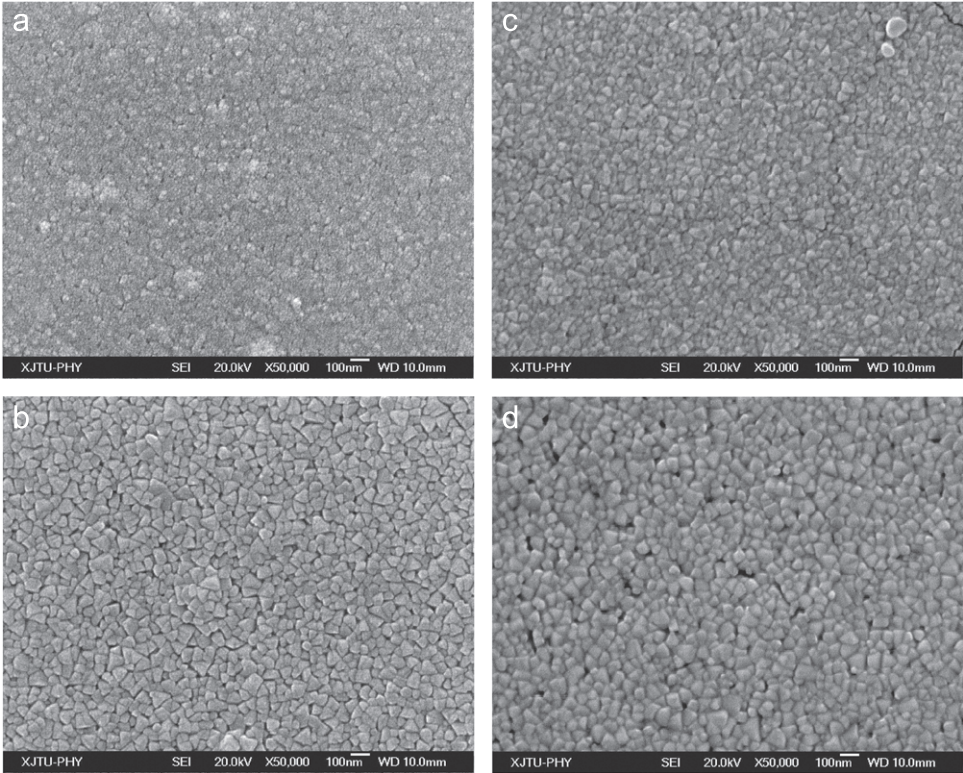


Fig. 2. SEM images of BaTiO<sub>3</sub> thin films deposited at (a) 2.9 Pa, (b) 3.5 Pa, (c) 4.0 Pa and (d) 4.5 Pa.

an inner tetragonal core, a gradient lattice strain layer (GLSL), and a surface cubic layer [9]. The lattice parameters ( $a$  and  $c$ ) change continuously in the middle layer GLSL. As a result, we can observe that the peaks around  $45^\circ$  were broad, indicating a slight splitting of (002)/(200) and a small tetragonal distortion.

### 3.2. Surface morphologies

The SEM surface micrographs of BaTiO<sub>3</sub> thin films deposited under different pressures are shown in Fig. 2. It can be seen that the grain size becomes larger with increasing working pressure.

At 2.9 Pa, the grain boundaries are not clear. The film deposited at 3.5 Pa shows clear grain boundaries. But the grain size is not uniform. The film deposited at 4.0 Pa exhibits a smooth and densely packed structure with homogeneous grains. The average grain size is about 80 nm. However, when deposited at higher pressure, like

4.5 Pa, the film exhibits more pores compared with the film prepared at 4.0 Pa.

The surface morphologies of BaTiO<sub>3</sub> thin films was examined by an atomic force microscope. Fig. 3 shows the results for the films deposited from 550 °C to 750 °C. The roughness in RMS with the different deposition temperatures is 3.0 nm, 5.1 nm, 2.4 nm, 8.5 nm and 11.4 nm, respectively. The roughness of the films significantly increases when deposited above 650 °C. This result can be attributed to the following: the energetic particle bombardment on the growing film that leads to the ejection of previously deposited atoms, and the formation of islands which grow large enough to touch and coalescence during nucleation and growth on the substrate [10]. For the substrate temperature from 650 °C to 750 °C, it is likely that the particles arrive in the substrate with high energy and cross the energy barrier of nucleation. These high energy particles are more likely to develop into films with high porosity and high roughness [11].

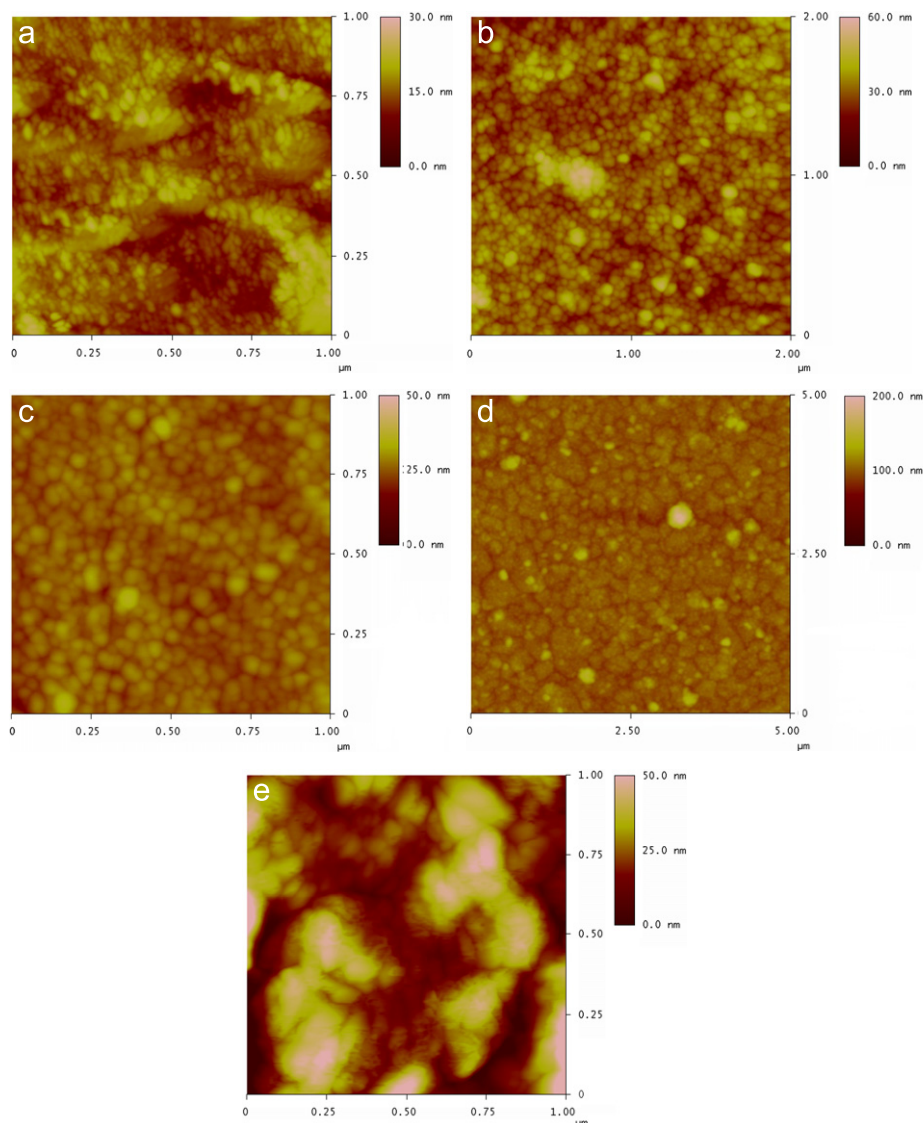


Fig. 3. AFM images of BaTiO<sub>3</sub> thin films deposited at (a) 550 °C, (b) 625 °C, (c) 650 °C, (d) 700 °C and (e) 750 °C.



### 3.3. Dielectric properties

Fig. 4 gives the relative permittivity ( $\epsilon_r$ ) and loss ( $\tan\delta$ ) of BaTiO<sub>3</sub> thin films measured at room temperature as a function of frequency. These films were deposited under the following parameters: 160 W, 5% O<sub>2</sub>, and the substrates temperature was set at 625 °C. The working pressure was set at 2.9 Pa, 3.5 Pa, 4.0 Pa and 4.5 Pa, respectively.

Fig. 5 gives the relative permittivity and loss tangent of BaTiO<sub>3</sub> thin films at 10 kHz. The film deposited under 4.5 Pa shows the improved properties with the relative permittivity of 630 and the loss of 2%.

The relative permittivity of BaTiO<sub>3</sub> thin films increases with working pressure. In BaTiO<sub>3</sub> ceramics, the relative permittivity decreases with increasing grain size. However, the tendency is reversed when the grain size is below a critical point, usually 1.1  $\mu\text{m}$  [12]. In this work, the average grain size of BaTiO<sub>3</sub> thin films was below 100 nm and the relative permittivity increases with grain size. As manifested in Fig. 4, the relative permittivity decreases in the high frequency range and the loss increases obviously in this range. The possible reasons are the hypothesis of the influence of the contact resistance between the probe and the electrode and the electrode resonance due to high relative permittivity [13]. Similar frequency dispersion phenomenon was also reported in other ferroelectric thin

films [14]. The dissipation factor in BaTiO<sub>3</sub> thin films is mainly caused by the contribution of the domain wall pinning, space charge polarization, interfacial diffusion, as well as secondary phases [15]. The dielectric loss remains low and steady as frequency is below 100 kHz.

The result suggests that the BaTiO<sub>3</sub> thin films are promising candidates for applications in thin film MLCCs [16].

### 4. Conclusion

BaTiO<sub>3</sub> thin films have been deposited under different deposition conditions. Crystallized BaTiO<sub>3</sub> thin films were deposited in the substrate temperature range from 550 °C to 750 °C. The films deposited from 550 °C to 625 °C show the (111) preferential orientation, while the films deposited above 650 °C show (110) preferential orientation. Weak tetragonal distortion was observed from the slight split in the (002)/(200) peaks indicating a pseudocubic phase occurred when the grain size decreased. The AFM and SEM images of the films show that the high substrate temperature led to large roughness. The grain size increases with working pressure. The film deposited at 625 °C and 4.5 Pa exhibits improved performance with the relative permittivity of 630 and the loss tangent of 2% at 10 kHz.

### Acknowledgments

This work was supported by the Natural Science Foundation of China (Grant no. 90923001), the International Science & Technology Cooperation Program of China (Grant nos. 2010DFB13640 and 2011DFA51880), the Shaanxi Province International Collaboration Program (Grant nos. 2009KW-12 and 2010KW-09), and the Shaanxi Science and Technology Promotion Program (2011TG-08).

### References

- [1] K. Ring, K. Kavanagh, Substrate effects on the ferroelectric properties of fine-grained BaTiO<sub>3</sub> films, *Journal of Applied Physics* 94 (9) (2003) 5982–5989.
- [2] Y.-K. Choi, T. Hoshina, H. Takeda, T. Teranishi, T. Tsurumi, Effects of oxygen vacancies and grain sizes on the dielectric response of BaTiO<sub>3</sub>, *Applied Physics Letters* 97 (21) (2010) 212907–212907-3.
- [3] H. Kozuka, S. Takenaka, H. Tokita, M. Okubayashi, PVP-assisted sol-gel deposition of single layer ferroelectric thin films over submicron or micron in thickness, *Journal of the European Ceramic Society* 24 (6) (2004) 1585–1588.
- [4] M.-H. Yeh, H.-F. Cheng, K.-S. Liu, I.-N. Lin, Characteristics of BaTiO<sub>3</sub> films prepared by pulsed laser deposition, *Japanese Journal of Applied Physics* 32 (1993) 5656–5660.
- [5] L. Preda, L. Courselle, B. Despax, J. Bandet, A. Ianculescu, Structural characteristics of RF-sputtered BaTiO<sub>3</sub> thin films, *Thin Solid Films* 389 (1–2) (2001) 43–50.
- [6] Y.K.V. Reddy, D. Mergel, S. Reuter, V. Buck, M. Sulkowski, Structural and optical properties of BaTiO<sub>3</sub> thin films prepared by radio-frequency magnetron sputtering at various substrate temperatures, *Journal of Physics D: Applied Physics* 39 (6) (2006) 1161–1168.

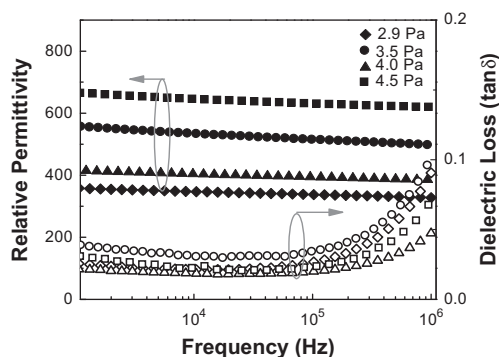


Fig. 4. Dielectric constant and loss tangent of the BaTiO<sub>3</sub> thin films deposited at 2.9 Pa, 3.5 Pa, 4.0 Pa and 4.5 Pa, respectively.

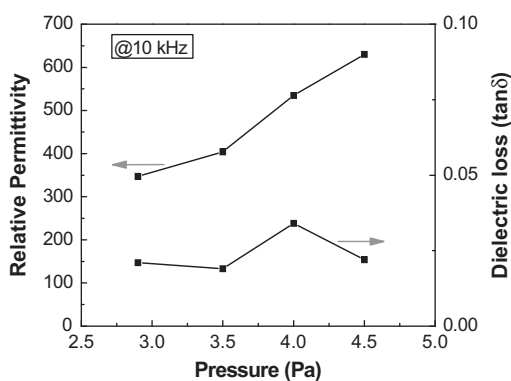


Fig. 5. Dielectric constant and loss tangent of BaTiO<sub>3</sub> thin films at 10 kHz.

- [7] B. Wang, L. Zhang, Size effects on structure and raman spectra of  $\text{BaTiO}_3$  thin films, *Physica Status Solidi* 169 (1) (1998) 57–62.
- [8] K. Yasukawa, M. Nishimura, Y. Nishihata, J. Mizuki, Core-shell structure analysis of  $\text{BaTiO}_3$  ceramics by synchrotron x-ray diffraction, *Journal of the American Ceramic Society* 90 (4) (2007) 1107–1111.
- [9] T. Hoshina, S. Wada, Y. Kuroiwa, T. Tsurumi, Composite structure and size effect of Barium Titanate nanoparticles, *Applied Physics Letters* 93 (19) (2008) 192914-1–192914-3.
- [10] C.-S. Hsi, F.-Y. Hsiao, N.-C. Wu, M.-C. Wang, Dielectric properties of nanocrystalline Barium Titanate thin films deposited by RF magnetron sputtering, *Japanese Journal of Applied Physics* 42 (2003) 544–548 (Part 1, No. 2 A).
- [11] S.-S. Lin, Effect of substrate temperature on the properties of  $\text{TiO}_2$  nanoceramic films, *Ceramics International* 38 (3) (2012) 2461–2466.
- [12] T. Hoshina, Y. Kigoshi, S. Hatta, H. Takeda, T. Tsurumi, Domain contribution to dielectric properties of fine-grained  $\text{BaTiO}_3$  ceramics, *Japanese Journal of Applied Physics* 48 (9) (2009) 09KC01-1–09KC01-4.
- [13] F.M. Pontes, D.S.L. Pontes, E.R. Leite, E. Longo, E.M.S. Santos, S. Mergulhao, A. Chiquito, P.S. Pizani, F. Lanciotti Jr, T.M. Boschi, J.A. Varela, Influence of Ca concentration on the electric, morphological, and structural properties of  $(\text{Pb,Ca})\text{TiO}_3$  thin films, *Journal of Applied Physics* 91 (10) (2002) 6650–6655.
- [14] P.C. Joshi, S.B. Krupanidhi, Structural and electrical studies on rapid thermally processed ferroelectric  $\text{Bi}_4\text{Ti}_3\text{O}_{12}$  thin films by metallo-organic solution deposition, *Journal of Applied Physics* 72 (12) (1992) 5827–5833.
- [15] Rasmi R. Das, P. Bhattacharya, Ram S. Katiyar, Enhanced ferroelectric properties in laser-ablated  $\text{SrBi}_2\text{Nb}_2\text{O}_9$  thin films on platinumized silicon substrate, *Applied Physics Letters* 81 (9) (2002) 1672–1674.
- [16] L. Huang, Z. Chen, J.D. Wilson, S. Banerjee, R.D. Robinson, I.P. Herman, R. Laibowitz, S. Brien, Barium Titanate nanocrystals and nanocrystal thin films: synthesis, ferroelectricity, and dielectric properties, *Journal of Applied Physics* 100 (3) (2006) 034316-1–034316-10.